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Entgegenhaltung 1:

JP Pat.-Offenlegung Nr. 11-171585 vom 29.06.1999

Anmeldung Nr. 10-278074 vom 30.09.1998

Priorität vom 02.10.1997, KR (Anm. Nr. 97P50968)

Anmelder: Samsung Electronics Co. Ltd., KR

Titel: Silikaglaszusammensetzung, und Verfahren zur
Herstellung von Silikaglas mittels dieser
Zusammensetzung

(Bemerkung:

Von der Anfertigung einer Übersetzung sehen wir ab, da diese
Offenlegung zu der US-PS 6.127.295 äquivalent ist.)

Silica glass composition and method for manufacturing silica glass using the same

Patent Number: ☐ US6127295
Publication date: 2000-10-03
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Requested Patent: ☐ JP11171585
Application Number: US19980165357 19981002
Priority Number(s): KR19970050968 19971002
IPC Classification: C03C3/04; C03B8/02
EC Classification: C03C3/06, C03C13/04D
Equivalents: CA2248492, CN1093090B, CN1213651, ☐ FR2769307, ☐ GB2329893, JP2971457B2, KR230457

Abstract

A silica glass composition and a method for manufacturing silica glass using the silica glass composition are provided. The silica glass composition includes: pyrogenetic silica having an average particle diameter of 5×10^{-3} to 1×10^{-1} μm and a specific surface area of 50 to 400 m^2/g ; and heat-treated silica, as an agglomerate of the pyrogenetic silica, having an average diameter of 2 to 15 μm and a specific surface area less than that of the pyrogenetic silica. A high purity silica glass tube, in which cracking after drying rarely occurs and the shrinking ratio is remarkably decreased, can be obtained by using the silica glass composition according to the present invention. Also, a large silica glass tube can be manufactured by using the composition.

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